Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L10	6110	probe same ((substrate material \$5film coat\$3 layer sheet pad wafer film lamina level plane) with silicon)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR S	NO	2005/03/22 10:10
Ξ	5611	110 and @ad<"20030922"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	SO.	NO	2005/03/22 10:10
L12	559	I11 and ((non\$1conduct\$5 dielectric insulat\$5 isolat\$5) adj (substrate material \$5film coat\$3 layer sheet pad wafer film lamina level plane)) with ((silicon adj nitride) (silicon adj oxide))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR.	NO	2005/03/22 10:11
113	7	112 and ((project\$5 protrud\$5 extend\$5) near2 (portion part member moiety parcel piece section segment)) with (conduct\$5 near2 (wir\$3 cord\$3 cabl\$3 line link channel connect\$5 lead\$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	NO	2005/03/22 10:12
114	2736	probe with ((substrate material \$5film coat\$3 layer sheet pad wafer film lamina level plane) with silicon)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	NO	2005/03/22 10:16
L15	2541	l14 and @ad<"20030922"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	S.	NO	2005/03/22 11:43
L16	248	115 and ((non\$1conduct\$5 dielectric insulat\$5 isolat\$5) adj (substrate material \$5film coat\$3 layer sheet pad wafer film lamina level plane)) with ((silicon adj nitride) (silicon adj oxide))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	NO	2005/03/22 10:17

117		116 and ((project\$5 protrud\$5 extend\$5) near2 (portion part member moiety parcel piece section segment)) with (conduct\$5 near2 (wir\$3 cord\$3 cabl\$3 line link channel connect\$5 lead\$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	%	N _O	2005/03/22 10:20
118	2403	probe with ((substrate material \$5film coat\$3 layer sheet pad wafer film lamina level plane) near5 silicon)	USPAT; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	NO O	2005/03/22 10:16
L19	2237	118 and @ad<"20030922"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR -	NO	2005/03/22 10:17
170	184	119 and ((non\$1conduct\$5 dielectric insulat\$5 isolat\$5) adj (substrate material \$5film coat\$3 layer sheet pad wafer film lamina level plane)) near5 ((silicon adj nitride) (silicon adj oxide))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	SO.	NO	2005/03/22 10:18
121	ហ	120 and ((project\$5 protrud\$5 extend\$5) near2 (portion part member moiety parcel piece section segment)) with thickness	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	NO	2005/03/22 10:20
77	155776	probe same (substrate material \$5film coat\$3 layer sheet pad wafer film lamina level plane)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR.	NO	2005/03/22 11:42
123	143412	l22 and @ad<"20030922"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	NO N	NO	2005/03/22 11:43

2005/03/22 13:04	2005/03/22 13:29	2005/03/22 13:29	2005/03/22 12:40	2005/03/22 12:41	2005/03/22 12:42	2005/03/22 12:42
NO	N O	N O	NO O	N O	N O	NO
OR OR	80 ·	S S	8 8	8 S	SO.	8
US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
I23 and ((project\$5 protrud\$5 extend\$5) near2 (portion part member moiety parcel piece section segment)) same (conduct\$5 near2 (wir\$3 cord\$3 cabl\$3 line link channel connect\$5 lead\$3)) same thickness	125 and (project\$5 protrud\$5 extend\$5) near2 (portion part member moiety parcel piece section segment) near3 thickness	125 and conduct\$5 near2 (wir\$3 cord\$3 cabl\$3 line link channel connect\$5 lead\$3) near3 thickness	(324/751,752,754,755,757,758.ccls.) and @ad<"20030922"	(324/72.5,715,765,158.1.ccls.) and @ad<"20030922"	(324/437,445-447.ccls.) and @ad<"20030922"	(324/690,696.ccls.) and @ad<"20030922"
61	S	7	5647	8919	395	624
1.25	127	671	P 9	131	132	133

134	12	I30 and (project\$5 protrud\$5 extend\$5) near2 (portion part member moiety parcel piece section segment) near3 thickness	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	SO.	NO	2005/03/22 12:45
135	11	131 and (project\$5 protrud\$5 extend\$5) near2 (portion part member moiety parcel piece section segment) near3 thickness	USPAT; USPAT; EPO; JPO; DERWENT; IBM_TDB	O S	NO	2005/03/22 13:01
136	0	132 and (project\$5 protrud\$5 extend\$5) near2 (portion part member moiety parcel piece section segment) near3 thickness	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	S.	NO O	2005/03/22 12:45
137	0	133 and (project\$5 protrud\$5 extend\$5) near2 (portion part member moiety parcel piece section segment) near3 thickness	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	NO	2005/03/22 12:45
138	28	I23 and pitch near3 (conduct\$5 near2 (wir\$3 cord\$3 cabl\$3 line link channel connect\$5 lead\$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	SO.	NO	2005/03/22 13:10
L39	н	I23 and (pitch near3 (conduct\$5 near2 (wir\$3 cord\$3 cabl\$3 line link channel connect\$5 lead\$3))) with micron	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	NO	2005/03/22 13:06
L40	1	I23 and (pitch near3 (conduct\$5 near2 (wir\$3 cord\$3 cabl\$3 line link channel connect\$5 lead\$3))) same micron	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	80 ·	NO	2005/03/22 13:17

L41	н	l23 and (pitch near3 (conduct\$5 near2 (wir\$3 cord\$3 cabl\$3 line link channel connect\$5 lead\$3))) same micro\$5	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	S.	NO NO	2005/03/22 13:20
L42	226	I23 and (conduct\$5 near2 (wir\$3 cord\$3 cabl\$3 line link channel connect\$5 lead\$3)) same thickness same width	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	NO	2005/03/22 13:23
L43	9	125 and (conduct\$5 near2 (wir\$3 cord\$3 cabl\$3 line link channel connect\$5 lead\$3)) same thickness same width	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	S S	NO	2005/03/22 13:24
44	75	I23 and conduct\$5 near2 (wir\$3 cord\$3 cabl\$3 line link channel connect\$5 lead\$3) near3 thickness	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	NO	2005/03/22 14:28
L45	0	144 and (project\$5 protrud\$5 extend\$5) near2 (portion part member moiety parcel piece section segment) near3 thickness	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	NO	2005/03/22 13:30
L46	o.	144 and (project\$5 protrud\$5 extend\$5) near2 (portion part member moiety parcel piece section segment) same thickness	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	NO	2005/03/22 13:30
L47	7	I23 and (conduct\$5 near2 (wir\$3 cord\$3 cabl\$3 line link channel connect\$5 lead\$3) near5 thickness) same (nano\$1meter "nm")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	SO	NO	2005/03/22 14:59

L48	r-I	l23 and (conduct\$5 near2 (wir\$3 cord\$3 cabl\$3 line link channel connect\$5 lead\$3) near5 pitch) same micro\$5	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ő .	NO	2005/03/22 15:08
L49	24	I23 and (conduct\$5 near2 (wir\$3 cord\$3 cabl\$3 line link channel connect\$5 lead\$3)) same pitch same micro\$5	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	SO .	NO	2005/03/22 15:15
L50	9	(conduct\$5 near2 (wir\$3 cord\$3 cabl\$3 line link channel connect\$5 lead\$3)) same (pitch near3 (("a" one "1") adj micro\$5))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	S S	N O	2005/03/22 15:17
151	ω	(conduct\$5 near2 (wir\$3 cord\$3 cabl\$3 line link channel connect\$5 lead\$3)) with (pitch near3 (("a" one "1") adj micro\$5))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	S.	NO	2005/03/22 15:18
L52	9	i50 and @ad<"20030922"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	S S	NO	2005/03/22 15:20
L53	Ŋ	l51 and @ad<"20030922"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	SA S	NO	2005/03/22 15:19
S1	181	(324/724.ccls.) and @ad<"20030922"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	SO .	NO	2005/03/16 16:44

25	419	(324/722,691.ccls.) and @ad<"20030922"	US-PGPUB; USPAT;	OR	NO	2005/03/22 15:18
			EPO; JPO; DERWENT; IBM_TDB		·	
S	242	(324/649,600.ccls.) and @ad<"20030922"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	NO	2005/03/22 12:39
S 4	80	S1 and probe same (substrate material \$5film coat\$3 layer sheet pad wafer film lamina level plane)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR.	NO	2005/03/17 09:46
. SS	55	S2 and probe same (substrate material \$5film coat\$3 layer sheet pad wafer film lamina level plane)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	S.	NO	2005/03/16 14:44
95	17	S3 and probe same (substrate material \$5film coat\$3 layer sheet pad wafer film lamina level plane)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	S S	NO	2005/03/16 14:44
22	17	S4 and (project\$5 protrud\$5 extend\$5) near2 (portion part member moiety parcel piece section segment)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	S.	NO	2005/03/17 09:42
88		S5 and (project\$5 protrud\$5 extend\$5) near2 (portion part member moiety parcel piece section segment)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	S S	NO	2005/03/16 16:27

65	2	S6 and (project\$5 protrud\$5 extend\$5) near2 (portion part member moiety parcel piece section segment)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	SO.	NO	2005/03/16 16:26
S10	-	S7 and ((project\$5 protrud\$5 extend\$5) near2 (portion part member moiety parcel piece section segment)) same (conduct\$5 near2 (wir\$3 cord\$3 cabl\$3 line link channel connect\$5))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	S S	NO	2005/03/17 09:52
S11	10	S7 and (conduct\$5 near2 (wir\$3 cord\$3 cabl\$3 line link channel connect\$5))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	NO	2005/03/16 15:05
S12	10	S7 and (conduct\$5 near2 (wir\$3 cord\$3 cabl\$3 line link channel connect\$5 lead\$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	NO	2005/03/16 15:07
S13	m	S8 and (conduct\$5 near2 (wir\$3 cord\$3 cabl\$3 line link channel connect\$5 lead\$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	S S	NO	2005/03/16 16:12
S14	17361	((non\$1conduct\$5 dielectric insulat\$5) adj (substrate material \$5film coat\$3 layer sheet pad wafer film lamina level plane)) with ((project\$5 protrud\$5 extend\$5) near2 (portion part member moiety parcel piece section segment))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	S S	NO	2005/03/17 09:48
S15	16524	S14 and @ad<"20030922"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	SO .	NO	2005/03/17 09:50

2005/03/22 11:42	2005/03/22 11:44	2005/03/17 09:56	2005/03/17 09:57	2005/03/22 09:58	2005/03/21 14:25	2005/03/21 14:25
NO	N O	N O	N O	N O	N O	Z O
SO.	SO.	8	& S	NO N	SA S	8
US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
S15 and probe same (substrate material \$5film coat\$3 layer sheet pad wafer film lamina level plane)	S16 and ((project\$5 protrud\$5 extend\$5) near2 (portion part member moiety parcel piece section segment)) same (conduct\$5 near2 (wir\$3 cord\$3 cabl\$3 line link channel connect\$5 lead\$3))	S16 and ((project\$5 protrud\$5 extend\$5) near2 (portion part member moiety parcel piece section segment)) with (conduct\$5 near2 (wir\$3 cord\$3 cabl\$3 line link channel connect\$5 lead\$3))	S18 and (plural\$5 number multipl\$5 series several set) adj2 (conduct\$5 near2 (wir\$3 cord\$3 cabl\$3 line link channel connect\$5 lead\$3))	((non\$1conduct\$5 dielectric insulat\$5) adj (substrate material \$5film coat\$3 layer sheet pad wafer film lamina level plane)) with ((project\$5 protrud\$5 extend\$5) near2 (portion part member moiety parcel piece section segment))	S20 and @ad<"20030922"	S21 and probe same (substrate material \$5film coat\$3 layer sheet pad wafer film lamina level plane)
477	110	70	16	17363	16526	477
S16	517	518	519	820	521	S22

523	70	70 S22 and ((project\$5 protrud\$5 extend\$5) near2 (portion part member moiety parcel piece section segment)) with (conduct\$5 near2 (wir\$3 cord\$3 cabl\$3 line link channel connect\$5 lead\$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR.	NO	2005/03/22 10:01
S24	7	Kenan near2 gad	US-PGPUB; OR USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	NO	2005/03/21 15:50